

Form PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Use several sheets if necessary)	ATTY. DOCKET NO. 2925-0329P	APPLICATION NO. NEW
	APPLICANT Sungho JIN et al.	
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U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
TS	5 4 2 6 6 8 6	1995-06-20	Rentzepis et al.			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

TS	W. DeVore et al., "High emittance electron gun for projection lithography", 1998 American Vacuum Society, J. Vac. Sci. Technol. B14(6), Nov./Dec., 1996, pp. 3764-3769
TS	W.K. Waskiewicz et al., "Design of a Low-Brightness, Highly Uniform Source for Projection Electron-Beam Lithography (SCALPEL)", Proc. SPIE, 3155, 1997
TS	J. Hasker et al., "Cathode and Scaling Properties Related to the Shape of Current-Voltage Characteristics", Applied Surface Science 24 (1985), pp. 318-329
TS	Robert Bakish, "Introduction to Electron Beam Technology", pp. 73-74

EXAMINER <i>Shelma Sheree Clove</i>	DATE CONSIDERED <i>7-31-01</i>
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